

FORM PTO-1449  INFORMATION DISCLOSURE CITATION IN AN APPLICATION  (Use several sheets if necessary)	Docket Number (Optional)	Application Number
	335.7735USU	Not Yet Assigned
	Applicant	
	Binod et al.	
Filing Date	Group Art Unit	
October 31, 2003	Not Yet Assigned	

## U. S. PATENT DOCUMENTS

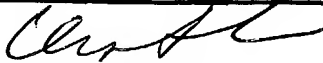
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
CMU	US 2002/0013059 A1	1/31/02	Kishimura et al.	438	694	
	US 2002/0182541 A1	12/5/02	Gonsalves	430	287.1	

## FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

## OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, Etc.)

CMU	Feher et al., "Facile Syntheses of New Incompletely Condensed Polyhedral Oligosilsesquioxane [c-(C <sub>3</sub> H <sub>9</sub> ) <sub>7</sub> Si <sub>7</sub> O <sub>9</sub> (OH) <sub>3</sub> ], [c-C <sub>7</sub> H <sub>13</sub> ) <sub>7</sub> Si <sub>7</sub> O <sub>9</sub> (OH) <sub>3</sub> ], and [c-C <sub>7</sub> H <sub>13</sub> ) <sub>6</sub> O <sub>7</sub> (OH) <sub>4</sub> ]", Organometallics, 1991, Pgs. 2526-2528.
	Joseph C. Salamone, "Silsesquioxane-Based Polymers", Polymeric Materials Encyclopedia Vol. 10, Q-S, 1996, Pgs. 7768-7778.
CMU	Lichtenhan et al., "Linear Hybrid Polymer Building Blocks: Methacrylate-Functionalized Polyhedral Oligomeric Silsesquioxane Monomers and Polymers", Macromolecules 1995, Pgs. 8435-8437.
	Lichtenhan et al. "Nanostructured chemicals: A new era in chemical technology", Chemical Innovation, Jan. 2001, Vol. 31, No. 1 Pgs. 1-5.
CMU	Joseph D. Lichtenhan, "Polyhedral Oligomeric Silsesquioxanes: Building Blocks for Silsesquioxane-Based Polymers and Hybrid Materials", Inorg. Chem. Vol. 17, No. 2, 1994, Pgs. 115-130.
	Wu et al., "Novel Positive-Tone Chemically Amplified Resists with Photoacid Generator in the Polymer Chains", Adv. Mater., 13, No. 9 May 2001, Pgs. 670-672

EXAMINER. 	DATE CONSIDERED 9/23/04
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP §609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

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<i>CM</i>	Wu et al., "Incorporation of polyhedral oligosilsesquioxane in chemically amplified resists to improve their reative ion etching resistance", J. Vac. Sci. Techno. B 19 (3), May/June 2001, Pgs. 851-855.
<i>CM</i>	Gonsalves et al., "Organic-Inorganic Nanocomposites: Unique Resists for Nanolithography", Adv. Mater. 2001, 13, No> 10, May 17, 2001, Pgs. 703-714.

EXAMINER <i>Curtis L</i>	DATE CONSIDERED <i>9/23/04</i>
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Sheet 1 of 1.

Application Number

10/699,298

## De et al.

Group Art Unit

1711

(Use several sheets if necessary)

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FILING DATE IF  
APPROPRIATE

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## FOREIGN PATENT DOCUMENTS

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NO

**OTHER DOCUMENTS** (including Author, Title, Date, Pertinent Pages, Etc.)

International Search Report Application No. PCT/US03/34832 dated 29 April 2004.

DATE CONSIDERED

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